

RECEIVED
CENTRAL FAX CENTER

JOHN P. TAYLOR
PATENT ATTORNEY
POST OFFICE BOX 1598
TEMECULA, CA 92593-1598
(909) 303-1416 (Telephone and Fax)

MAY 23 2005

FACIMILE TRANSMISSION COVER SHEET

To: Honorable Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:

Appl. No.: 10/619,978
 Applicants: Yong-Bae Kim and Philippe Schoenborn
 Filed: July 14, 2003
 TC./A.U.: 1765
 Examiner: Kin-Chan Chen
 Title: PROCESS FOR REMOVAL OF PHOTORESIST MASK USED FOR MAKING VIAS
 IN LOW K CARBON-DOPED SILICON OXIDE DIELECTRIC MATERIAL, AND
 FOR REMOVAL OF ETCH RESIDUES FROM FORMATION OF VIAS AND
 REMOVAL OF PHOTORESIST MASK
 Docket No.: 01-125/1C

CERTIFICATION OF FACSIMILE TRANSMISSION	
I hereby certify that the accompanying amendment is being facsimile transmitted to the Patent and Trademark Office (Fax No. (703) 872-9306) on the date shown below,	
on	May 23, 2005 (Date of Facsimile Transmission)
John P. Taylor, Reg. No. 22,369	
 Signature	
May 23, 2005 Date of Signature	

Total Pages (including this cover sheet): 16

Documents included:

Fax Cover Sheet	1 Pages
Amendment Transmittal Letter	2 Pages
Amendment	11 Pages
Terminal Disclaimer	2 Pages

Missing 14 Pages

* Received: 2 pages. CT

AMENDMENT TRANSMITTAL LETTER			ATTORNEY'S DOCKET NO. 01-125/1C
SERIAL NO. 10/619,978	FILING DATE July 14, 2003	EXAMINER Kin-Chan Chen	GROUP ART UNIT 1765
INVENTION PROCESS FOR REMOVAL OF PHOTORESIST MASK USED FOR MAKING VIAS IN LOW K CARBON-DOPED SILICON OXIDE DIELECTRIC MATERIAL, AND FOR REMOVAL OF ETCH RESIDUES FROM FORMATION OF VIAS AND REMOVAL OF PHOTORESIST			